

Electron Beam Lithography System ELS-BODEN

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High Performance Capabilities for High Resolution and High Throughput Applications



ELS-BODEN
Acceleration 100kV × Single Autoloader

Available in 8-inch and 12-inch Chambers

The first full 12-inch exposure area in the marketplace. Capable of handling small samples often used for research purposes, as well as 2/3/4/5/6/7/8/12 inch wafers, and mask holders, for the 6025 and 9025 mask sizes.

Complete Line of Automatic Loading Systems

Single cassette autoloader, which is useful for research and development applications. Multiple cassette autoloader for small to medium volume production. A full lineup of robot loading systems.

User-friendly Software

New software "elms" is installed as a standard feature. By segmenting various functions such as CAD condition, beam condition, exposure, and SEM observation, it has become significantly easier to find the necessary features and enables you to enhance your productivity. With the account management feature, you can restrict the functionalities based on the user's level.

Specifications

Electron Gun	ZrO/W Thermal Field Emitter				Max. Sample Size	8" Wafer / 12" Wafer
Acceleration Voltage	50 kV	100 kV	125 kV	150 kV	Max. Exposure Area	200 mm x 200 mm / 300 mm x 300 mm
Beam Current	1 nA ~ 800 nA	20 pA ~ 200 nA	5 pA ~ 100 nA	5 pA ~ 100 nA	Loading System	Single Autoloader Multi Autoloader Robot Loader
Min. Beam Spot Size	D 2.8 nm	D 1.8 nm	D 1.7 nm	D 1.5 nm		
Exposure Field Size	1000 μm□	1000 μm□	500 μm□	500 μm□	Software	elms • Beam Conditions • Python Scripting • Exposure Schedule • Pattern Data Converter • Account Management
Min. / Max. Field Size	Min. 100 μm □ Max. (Option) 3000 μm □					
Scan Clock	100 MHz Max. (Option) 200 MHz					
Shot Pitchi	Min. 0.2 nm					

